



mmeC

USE OF SYNCHROTRONS IN SEMICONDUCTOR R&D

PAUL VAN DER HEIDE

SEMICONDUCTORS



INTEGRATED CIRCUITS (IC)

HVM

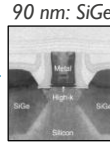


Min. feature size: 1.5 μm

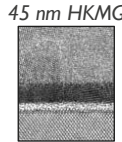


Min. feature size: 0.8 μm

Dennard scaling

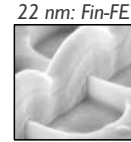


90 nm: SiGe



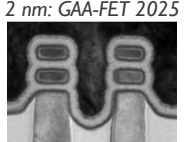
45 nm HKMG

2D $\rightarrow$ 3D



22 nm: Fin-FET

Fin-FET $\rightarrow$ GAA



2 nm: GAA-FET 2025

Images from: [List of Intel processors - Wikipedia](#)

1980s

1990s

2000s

2010s

2020s



Image from: [ENIAC - Wikipedia](#)

Computer in 1946

- 18000 vacuum tubes
- Weighed more than 25 tons
- 5000 operations per second
- Cost \$ 500,000 (~\$7 million today)



First transistor (replica), Bell Labs, 1947

The first transistor used two closely spaced gold contacts pressed onto the surface of a slab of high-purity germanium.



1970s

1971: Intel 4004

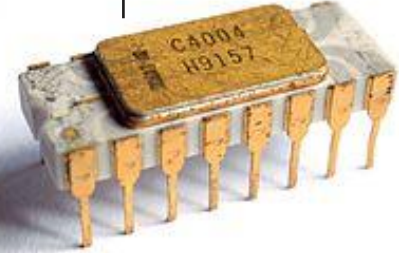
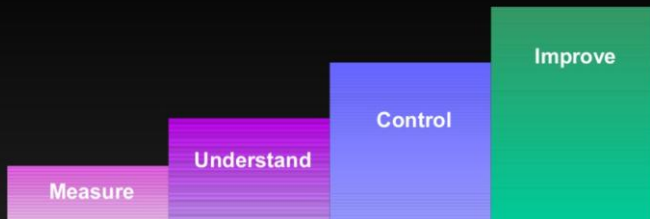


Image from: [Inventing the Transistor - CHM Revolution \(computerhistory.org\)](#)

Image from: [Intel 4004 - Wikipedia](#)

THE IMPORTANCE OF MEASUREMENT



If you can't **measure** it, you can't **understand** it.

If you can't **understand** it, you can't **control** it.

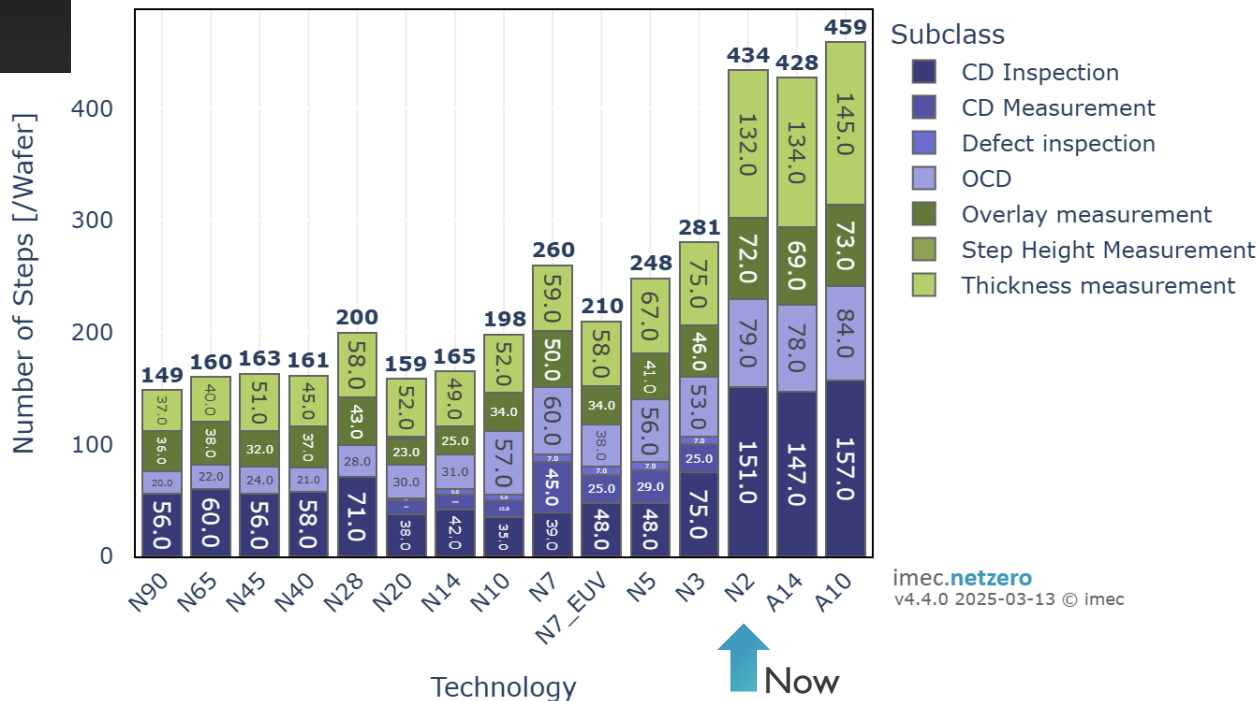
If you can't **control** it, you can't **improve** it.

Metrology need

- HVM: Process control →
 - Enabling ROI
- R&D: Understanding
 - Enabling next-gen ICs to remain competitive

THE NEED FOR MEASUREMENT

Comparison of Number of Steps [/Wafer] by Technology & Subclass for Process
Area = METROLOGY (official)



IMEC FORECASTS

■ CMOS scaling for memory, logic & interconnect

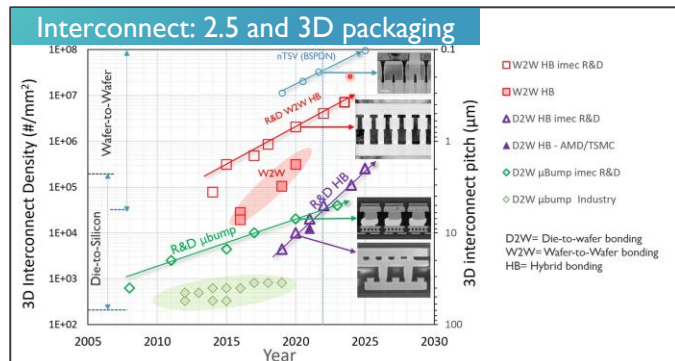
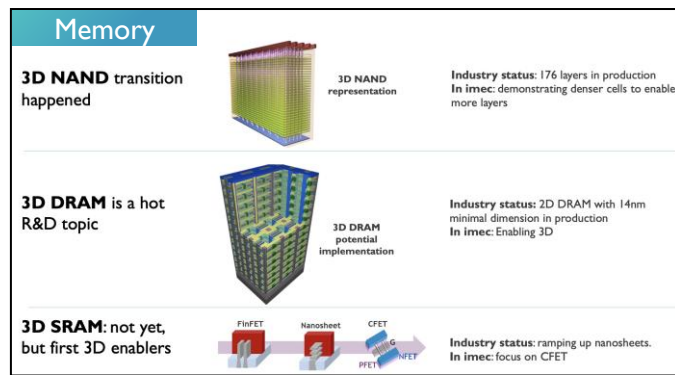
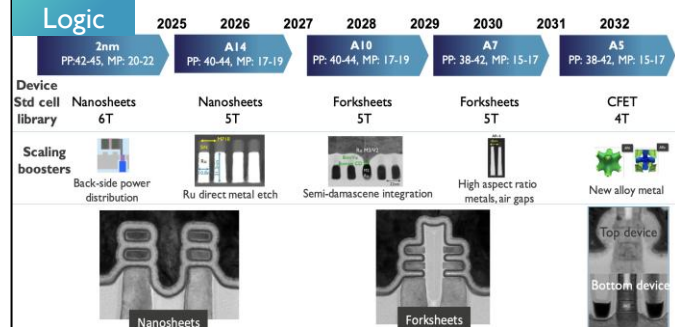
- New architectures, 3D, D2W, ...
 - New materials, HZO, IGZO, ...
- More complex analysis needed faster*

■ Beyond CMOS for memory, logic & interconnect

- 2D materials
 - Graphene
 - TMDs
 - CNTs
- New measurement requirements (mobility, spin, spin dynamics, ...)*

■ Beyond von Neuman (quantum compute)

- Josephson junction?
 - Si spin qubit, ...?
- Required metrologies to be defined*



PHOTOELECTRON EMISSION TECHNIQUES (XPS, PES, ...)

IN SYNCHROTRON, LAB & FAB ENVIRONMENTS

Synchrotron / Lab (offline)

- Fundamental understanding
- Path finding (exploration)
- Implementation (testing)

Primarily supports R&D

Lab (offline) / Fab (inline)

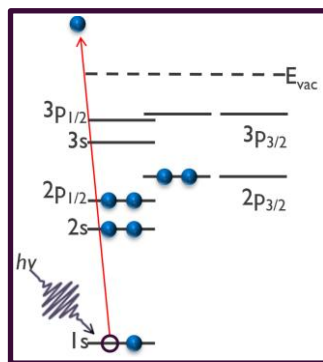
- Process development
- Process refinement
- Quality control

Primarily supports production



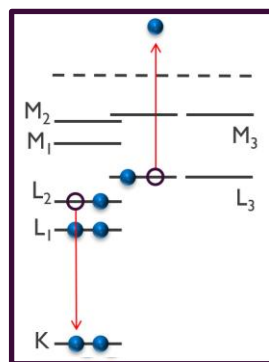
PHOTOELECTRON EMISSION (BASES OF XPS, PES, ...)

Photoelectron emission

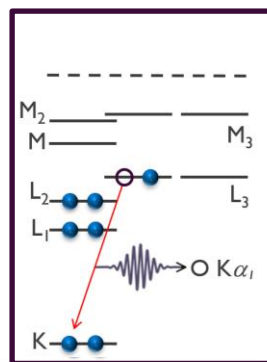


And then ($\sim 10^{-15}$ s later)

Auger electrons



Fluorescence



EDX
XRF
XES
etc.

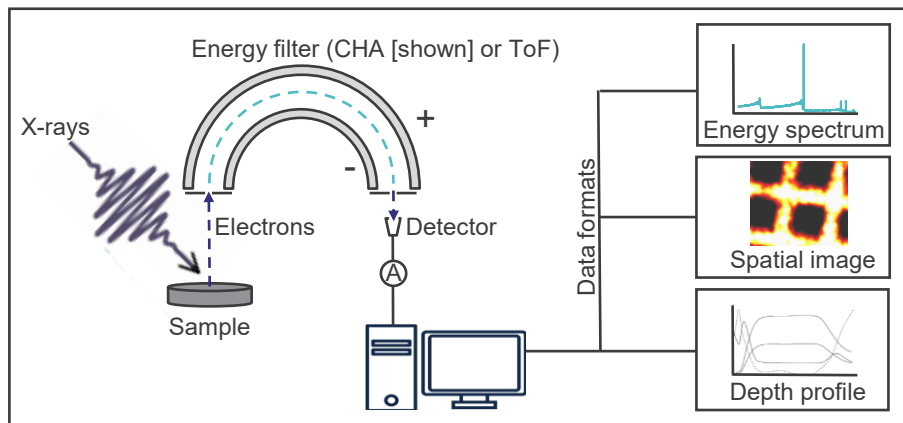
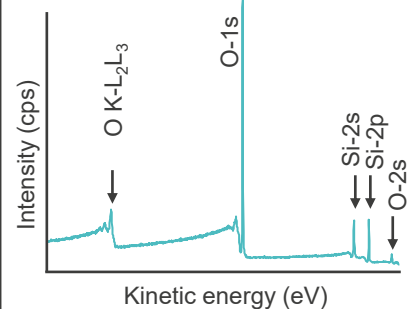


Photo and Auger electrons are recorded



PES inclusive of
XAFS and
ARPES, are also
photoelectron
techniques.

These are
primarily
carried out at
synchrotrons.

XPS VERSUS PES...

BOTH STEM FROM THE SAME PHYSICAL PROCESS (PHOTOELECTRON EMISSION)

XPS (including HAXPES)

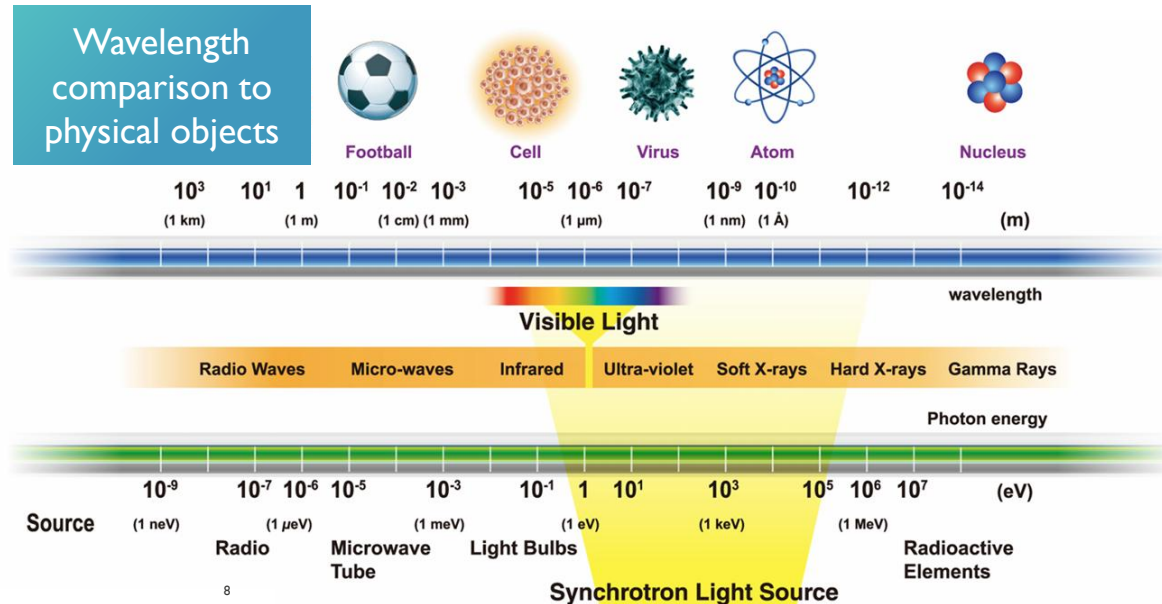
- Developed for carrying out quantitative surface analysis inclusive of speciation analysis
- A photon beam that is of fixed energy and that is unpolarized is optimal
- Anode sources are best as these are cheap and compact

PES (including XAFS & ARPES)

- Developed for carrying out experiments in condensed matter physics
- A photon beam that can be scanned in energy and/or polarized is optimal
- Synchrotron sources deemed best (highest flux and flexibility)

WHAT ARE SYNCHROTRONS

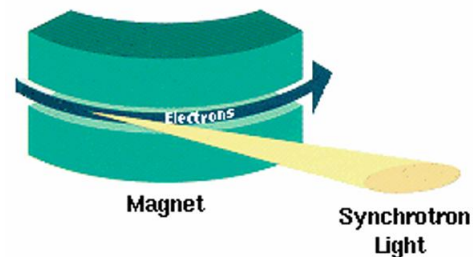
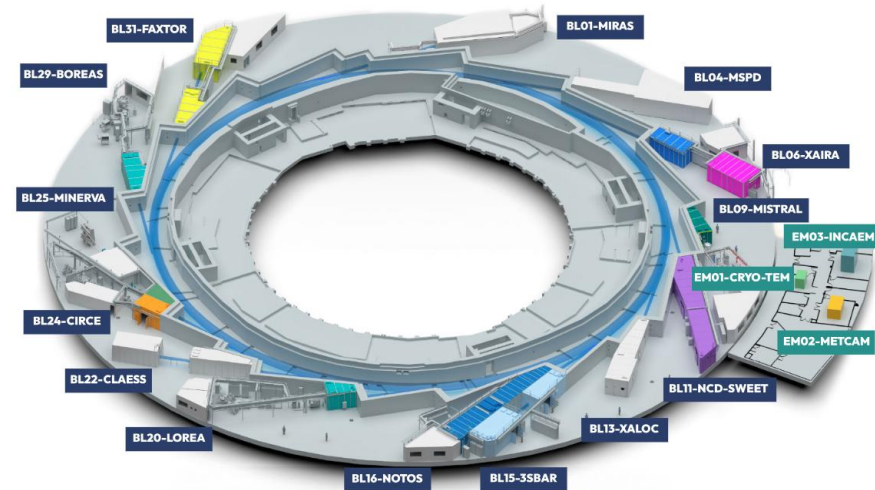
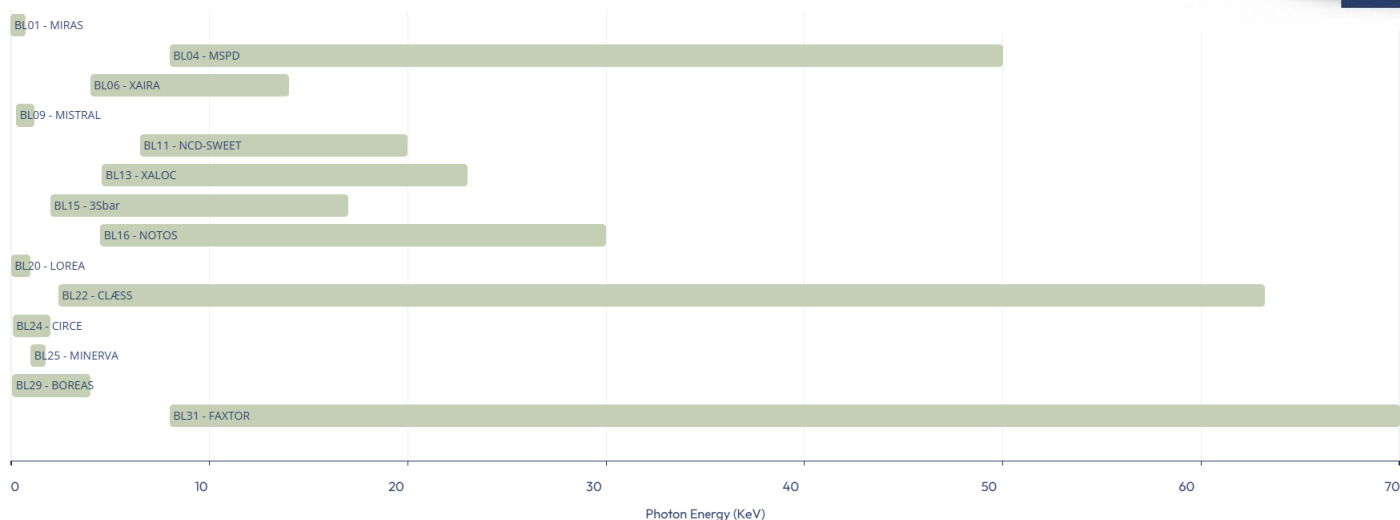
- These are among the brightest man-made light sources that extends into the X-ray regime
- These enable for the most sensitive metrologies
 - Orders of magnitude more sensitive than lab/fab-based metrology platforms
- But these are large facilities
 - Orders of magnitude larger than lab/fab-based platforms



THE ALBA SYNCHROTRON

- Photons are produced as electrons traveling at near relativistic speeds are forced to follow near circular paths

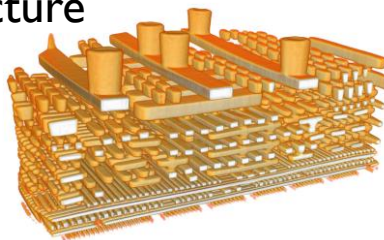
EXPLORE BEAMLINES BY PHOTON ENERGY RANGE



EXPERIMENTAL POSSIBILITIES

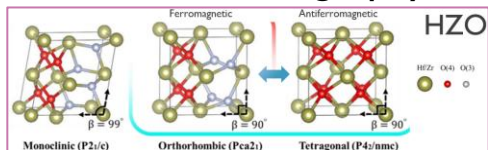
- Imaging of physical structure

- XCT to ptychography



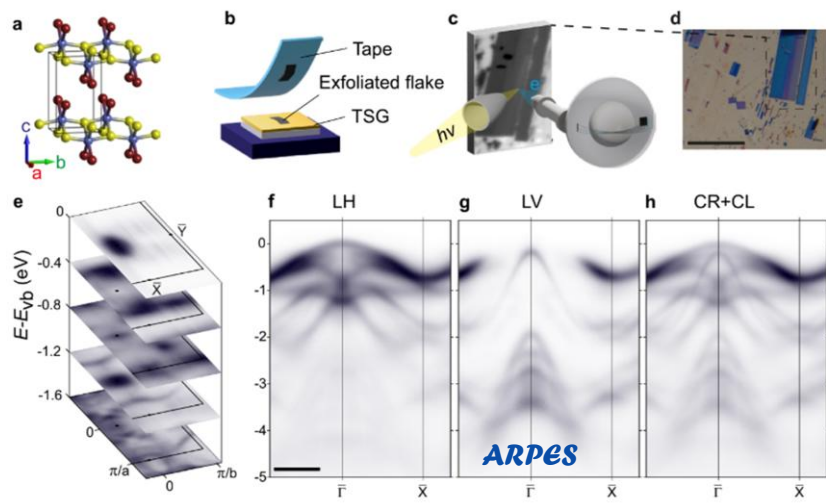
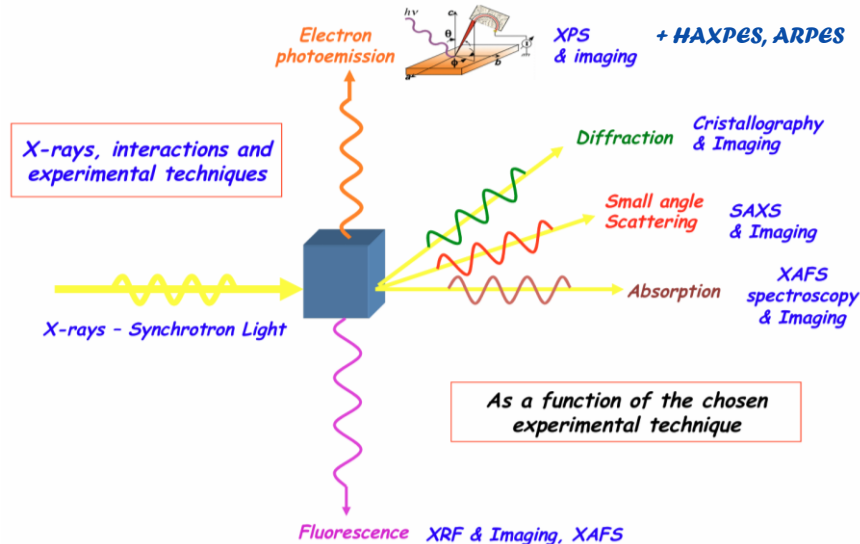
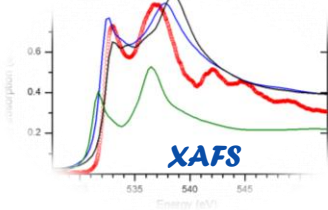
- Lattice structure (crystalline)

- Diffraction to photoelectron holography



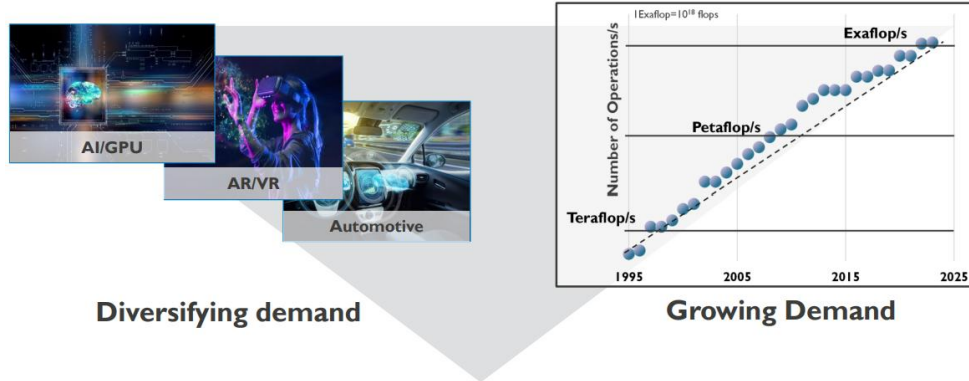
- Chemistry (speciation, electronic structure)

- XAFS to ARPES, ...

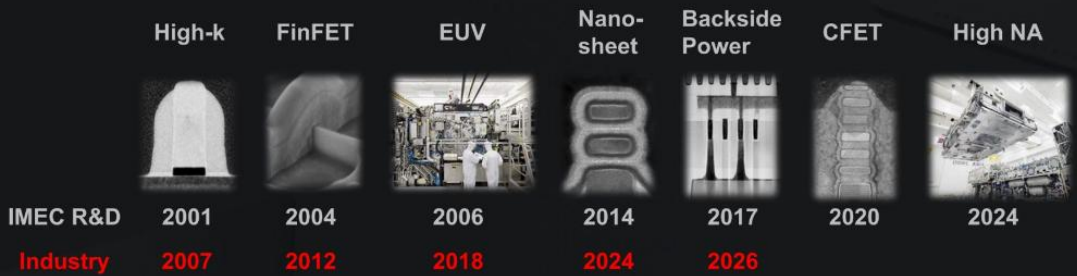


FUTURE

- More demand (AI driven)
- More diversity (TMDs, CNTs, ...)
- Imec R&D starts ~10 years earlier
 - Builds on academic R&D which starts even earlier



IMEC R&D's Valuable Contributions



Longer term

- Spintronics in logic and memory
 - Note: Spintronics is already used in Magneto-resistive RAM (MRAM)
- Move from ferromagnetic to antiferromagnetic memory? (is altermagnetism the next frontier?)



embracing a better life